

Title (en)

Film formation method, method for fabricating electron emitting element employing the same film, and method for manufacturing image forming apparatus employing the same element

Title (de)

Filmformationsverfahren, Verfahren zur Herstellung eines elektronenemittierenden Elementes mit einem solchen Film, und Verfahren zur Herstellung eines Bilderzeugungsgerätes mit einem solchen Element

Title (fr)

Méthode de formation d'une couche, procédé de fabrication d'un élément émetteur d'électrons utilisant cette couche, et procédé de fabrication d'un appareil de formation d'images utilisant cet élément

Publication

EP 0936652 B1 20061213 (EN)

Application

EP 99301022 A 19990212

Priority

- JP 4633598 A 19980213
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- JP 2993099 A 19990208

Abstract (en)

[origin: EP0936652A1] Disclosed is a method, for forming a film locally on a substrate, which comprises the steps of detecting the state of the substrate employing the obtained result to calculate positional information concerning a plurality of locations at which the material for the film is to be provided to form the film, and providing the material for the film at the plurality of locations based on the positional information that is obtained for the plurality of locations. <IMAGE>

IPC 8 full level

H01J 9/02 (2006.01); **B41J 2/01** (2006.01); **G09F 9/313** (2006.01); **H05K 3/12** (2006.01)

CPC (source: EP KR US)

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Citation (examination)

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Cited by

US8075944B2; CN1305094C; CN1327469C; US7442406B2; US6992434B2; US7264842B2; US6787984B2; US7211943B2; US6903504B2; US7097530B2

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